

ABSTRACT**Lithographic Apparatus and Device Manufacturing Method**

A lithographic apparatus is provided comprising an illumination system IL for providing a
 5 projection beam of radiation, a support structure MT for supporting patterning means M, the
 patterning means serving to impart the projection beam with a pattern in its cross-section, a
 substrate table WT for holding a substrate W, a projection system PL for projecting the patterned
 beam onto a target portion of the substrate W, a reference frame MF on which at least one of
 position sensors IF for at least one of said patterning means M and said substrate W, and said
 10 projection system MF are located, the apparatus further comprises a heat transport system HT-PL,
 HT-MF, in thermal interaction with at least one of the projection system PL and the reference frame
 MF, for heat transport to or from at least one of the projection system PL and the reference frame
 MF, wherein the heat transport system HT-PL, HT-MF is coupled to a further frame which is
 mechanically isolated from the reference frame MF.

Fig. 1

